

**ABSTRACT**

A substrate processing apparatus having substrate holding mechanisms for  
5 holding a substrate under a holding force which is changed according to a rotational  
speed of the substrate holding mechanisms, a substrate rotation mechanism for  
rotating the substrate holding mechanisms to rotate the substrate held by the  
substrate holding mechanisms, and a treatment liquid supply mechanism for  
supplying a treatment liquid to a desired portion of the substrate held by the  
10 substrate holding mechanisms.